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CONFIRMATION NO. 1510

SERIAL NUMBER 10/522,036	FILING DATE 01/19/2005  RULE	CLASS 430	GROUP ART UNIT 1752	ATTORNEY DOCKET NO. SHIGA7.004APC
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## APPLICANTS

Kenji Maruyama, Kawasaki-shi, JAPAN;

Masaki Kurihara, Kawasaki-shi, JAPAN;

Ken Miyagi, Kawasaki-shi, JAPAN; Satoshi Niikura, Kawasaki-shi, JAPAN;

Satoshi Shimatani, Kawasaki-shi, JAPAN;

Masahiro Masujima, Kawasaki-shi, JAPAN;

Kazuyuki Nitta, Kawasaki-shi, JAPAN;

Toshihiro Yamaguchi, Kawasaki-shi, JAPAN;

Kousuke Doi, Kawasaki-shi, JAPAN;

## \*\* CONTINUING DATA \*\*\*\*\*

This application is a 371 of PCT/JP04/07139 05/19/2004 SJL

## \*\* FOREIGN APPLICATIONS \*\*\*\*\*

JAPAN 2003141805 05/20/2003 ) SJL  
 JAPAN 2003426503 12/24/2003 )

Foreign Priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no	STATE OR	SHEETS	TOTAL	INDEPENDENT
35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after	COUNTRY	DRAWING	CLAIMS	CLAIMS
Verified and Acknowledged	JAPAN	0	38	4
Examiner's Signature <i>[Signature]</i> Initials SJL				

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## TITLE

Chemically amplified positive photo resist composition and method for forming resist pattern



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